

## PATENT APPLICATION

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re the Application of

Yuji IMAI Group Art Unit: 2851

Application No.: 10/791,810 Examiner: H. Nguyen

Filed: March 4, 2004 Docket No.: 109325.01

For: METHOD FOR EVALUATING LITHOGRAPHY SYSTEM, METHOD FOR ADJUSTING

SUBSTRATE-PROCESSING APPARATUS, LITHOGRAPHY SYSTEM, AND

**EXPOSURE APPARATUS** 

## **INFORMATION DISCLOSURE STATEMENT**

Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

Sir:

Pursuant to 37 CFR §1.56, the attention of the Patent and Trademark Office is hereby directed to the reference(s) listed on the attached PTO-1449. Unless otherwise indicated herein, one copy of each reference is attached. It is respectfully requested that the information be expressly considered during the prosecution of this application, and that the reference(s) be made of record therein and appear among the "References Cited" on any patent to issue therefrom.

- 1. This Information Disclosure Statement is being filed more than three months after the U.S. filing date and after the mailing date of a Final Rejection, Notice of Allowance, or other action that closes prosecution (e.g., Quayle Action), but before payment of the Issue Fee. Attached is our Check No. 161179 in the amount of \$180.00 in payment of the fee under 37 CFR §1.17(p). Please credit or debit Deposit Account No. 15-0461 as needed to ensure consideration of the disclosed information. Two duplicate copies of this paper are attached.
  - a. I hereby certify that each item of information contained in this Information Disclosure Statement was first cited in any communication from a foreign patent office in a counterpart foreign application not more than three months prior to the filing of this Information Disclosure Statement.

    37 CFR §1.97(e)(1).
- 2. Each item of information contained in this Information Disclosure Statement was cited in a communication from a foreign patent office in a counterpart application, and this communication was not received by any individual designated in §1.56(c) more than thirty days prior to the filing of this Information Disclosure Statement.

- 3. The reference(s) was/were cited in a counterpart foreign application. An English language version of the foreign search report is attached for the Examiner's information.
- 4. In accordance with 37 CFR §1.98(a)(2)(i), copies of any U.S. patents and patent application publications are not attached.

Respectfully submitted,

Mario A. Costantino Registration No. 33,565

MAC/ccs

Date: December 1, 2004

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INFORMATION DISCLOSURE STATEMENT										
(Use several sheets if necessary)		APPLICANT(S) Yuji IMAI								
		FILING DATE March 4, 2004		GROUP 2851						
U.S. PATENT DOCUMENTS										
EXAMINER INITIAL	DOCUMENT NUMBER		DATE	NAME			CLASS	SUB CLASS		
	4,908,656	03-13-1990		Suwa et al.						
· · · · · · · · · · · · · · · · · · ·	5,815,594	09-29-1998		Tanaka						
	5,252,414	10-12-1993		Yamashita et al.						
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				Fitle, Date, Pertinent Pages, etc.)						
	SPIE Vol. 1464 Integrated Circuit Met latent images to improve lithography co	SPIE Vol. 1464 Integrated Circuit Metrology, Inspection, and Process Control V (1991), "Use of diffracted light from latent images to improve lithography control", K.C. Hickman et al., pages 245-257.								
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EXAMINER DATE CONSIDERED										
Examiner: Initial if citation considered, whether or not citation is in conformance with M.P.E.P. 609; draw line through citation if not in conformance and not considered. Include conv. of this form with next communication to applicant										
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